

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)

Takashi YODA et al.)

Serial No.: Not Yet Assigned)

Filed: September 17, 2003)

For: SEMICONDUCTOR DEVICE AND)
METHOD OF MANUFACTURING THE SAME)

Group Art Unit: Not Yet Assigned

Examiner: Not Yet Assigned

MAIL STOP PATENT APPLICATION
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§1.56 and 1.97(b), applicants bring to the Examiner's attention the documents listed on attached Form PTO-1449. With exception of the U.S. patent, copies of the listed documents are attached. Applicants respectfully request that the Examiner consider the documents listed on attached Form PTO-1449 and indicate that they were considered by making an appropriate notation on this form. This Information Disclosure Statement is being filed with the above-referenced application.

The following are listed on the accompanying PTO-1449 and are in a non-English language:

1. Japanese Patent Publication No. 2002-110789 - The relevance of this document is discussed at page 3 of the specification of the present application.
2. Japanese Patent Publication No. 2002-176054 – discloses forming of a mixed layer between a low dielectric constant insulating film and a barrier metal film.

FINNEGAN
HENDERSON
FARABOW
GARRETT &
DUNNER LLP

1300 I Street, NW
Washington, DC 20005
202.408.4000
Fax 202.408.4400
www.finnegan.com

Also, an English-language abstract of each document is enclosed.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicants determine that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the office the relevant facts and law regarding the appropriate status of such documents. Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: September 17, 2003

By: 

Richard V. Burgujian
Reg. No. 31,744

Enclosures
RVB/FPD/sci

INFORMATION DISCLOSURE CITATION

Atty. Docket No. 04329.3140	Serial No. Not Yet Assigned
Applicants Takashi YODA et al.	
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U.S. PATENT DOCUMENTS							
Examiner Initial*		Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
		2003-0116854-A1	06/26/03	ITO et al.			

FOREIGN PATENT DOCUMENTS							
		Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
		2002-110789	04/12/02	JAPAN			ABSTRACT
		2002-176054	06/21/02	JAPAN			ABSTRACT

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
	LIN, J. C. et al., "CVD Barriers for Cu with Nanoporous Ultra Low-k: Integration and Reliability", International Interconnect Technology Conference, pp. 21-23, (2002).
	MOSIG, K. et al., "Integration of Porous Ultra Low-k Dielectric with CVD Barriers", International Electron Device Meeting, pp. 88-91, (2001).

Examiner	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce